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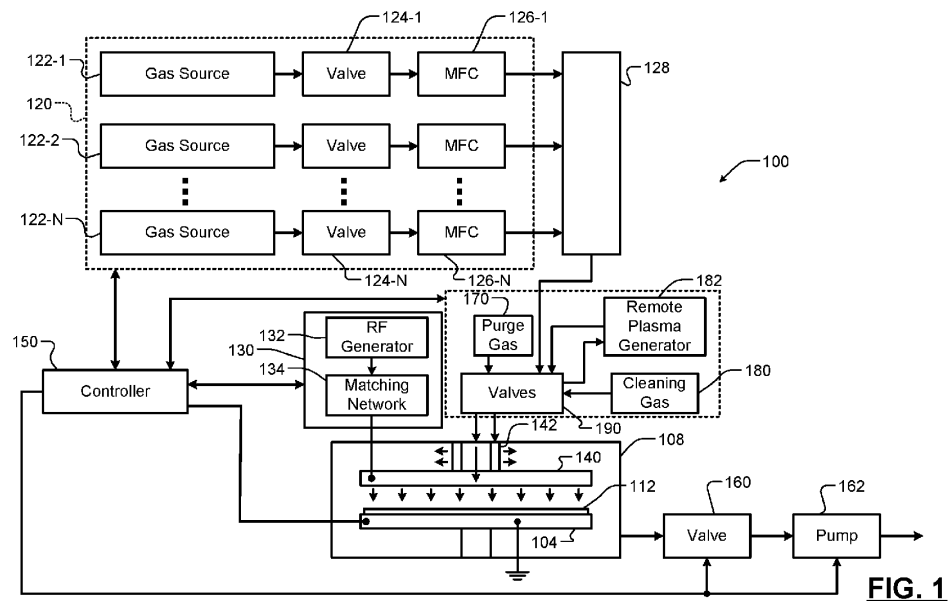
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(54) Title: APPARATUS FOR CLEANING PLASMA CHAMBERS



(57) Abstract: Systems and methods for cleaning a processing chamber include supplying a pre-activated cleaning gas through a collar surrounding a showerhead stem into the processing chamber to clean the processing chamber. In other embodiments, a cleaning gas is supplied to the collar, and RF power is supplied to the showerhead or to a pedestal to generate plasma in the processing chamber to clean the processing chamber. In still other embodiments, an inert gas is supplied to the collar, a pre-activated cleaning gas is supplied to the showerhead stem, and RF power is supplied to the showerhead or to the pedestal to generate plasma in the processing chamber to clean the processing chamber.

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Declarations under Rule 4.17:

- *as to applicant's entitlement to apply for and be granted a patent (Rule 4.17(ii))*
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